MAR 4 2003 REFERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 219625US99DIV

APPLICANT

SERIAL NO. 10/076,450

Jamal Ramdani et al

1	4 2003 REFERENCES CITED BY APPLICANT		Jamal Ramdani et al						
•	7 400	8				FILING DATE February 19, 2002		GROUP	2815
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٦	EXAM	INER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
╟	1 1	}}	AA	3,802,967	04/09/74	Ladany et al.		CLASS	IFAFFROFRIATE
∦	II() IV	-	ÁB	4,174,422	11/13/79	Matthews et al.			
ł	1		AC	4,404,265	09/13/83	Manasevit			.
╟	1		AD	4,482,906	11/13/84	Hovel et al.			
╽			AE	4,523,211	06/11/85	Morimoto et al.			
I			AF	4,661,176	04/28/87	Manasevit			· · · · · · · · · · · · · · · · · · ·
I			AG	4,793,872	12/27/88	Meunier et al.			
╽			АН	4,846,926	07/11/89	Kay et al.			
I	•		AJ	4,855,249	08/08/89	Akasaki et al.			
ı			ΑI	4,891,091	01/02/90	Shastry			
ľ	Ī		AK	4,912,087	03/27/90	Aslam et al.			
ľ			AL	4,928,154	05/22/90	Umeno et al.			
ı			АМ	4,963,949	10/16/90	Wanlass et al.			
ľ			AN	5,141,894	08/25/92	Bisaro et al.			
I			AO	5,159,413	10/27/92	Calviello et al.			
ľ			AP	5,173,474	12/22/92	Connell et al.			
ľ			AQ	5,221,367	06/22/93	Chisholm et al.			
ı			AR	5,225,031	07/06/93	McKee et al.			
ľ			AS	5,358,925	10/25/94	Neville Connell et al.			
			ΑT	5,393,352	02/28/95	Summerfelt			
			AU	5,418,216	05/23/95	Fork			
			AV	5,450,812	09/19/95	McKee et al.			
	4		AW	5,478,653	12/26/95	Guenzer			
			AX	5,482,003	01/09/96	McKee et al.			
			AY	5,514,484	05/07/96	Nashimoto			
			AZ	5,556,463	09/17/96	Guenzer			
			1	5,588,995	12/31/96	Sheldon			
				5,670,798	09/23/97	Schetzina			
		l	l	5,733,641	03/31/98	Fork et al.			
				5,735,949	04/07/98	Mantl et al.			
		<u> </u>	BE	5,741,724	04/21/98	Ramdani et al.			
			BF	5,810,923	09/22/98	Yano et al.			
		1	1	5,830,270	11/03/98	McKee et al.			
				5,912,068	06/15/99	Jia			
			BI	6,020,222	02/01/00	Wollesen			· ····
∦			BJ	6,045,626	04/04/00	Yano et al.			
				6,064,078	05/16/00	Northrup et al.		 	
-		1	BL	6,064,092	05/16/00	Park			
		-	BM	6,096,584	08/01/00	Ellis-Monaghan et al.			
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-				6,136,666	10/24/00	So Magning			
		 	BP	6,174,755	01/16/01	Manning Lookandung et al.			
			BQ	6,180,486	01/30/01	Leobandung et al.			

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 219625US99DIV SERIAL NO. 10/076,450

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KW)	CA	3,766,370	02/08/77				
10 1		СВ	4,006,989		Andringa	-		
		CC	4,284,329	08/18/81	Smith et al.	ļ		
		CD	4,777,613	10/11/98	Shahan et al.	ļ		
		CE	4,802,182	01/31/89	Thornton et al.	4		
		CF	4,882,300	11/21/89	Inoue et al.			
		CG	4,896,194	01/23/90	Suzuki	<u> </u>		
		СН	4,999,842	03/12/91	Huang et al.	j		
		CI	5,081,062	01/14/92	Vasudev et al.	į		
		C1	5,155,658	10/13/92	Inam et al.			
		СК	5,248,564	09/28/93	Ramesh			
		CL	5,260,394	11/09/93	Tazaki et al.			
		СМ	5,270,298	12/14/93	Ramesh			_
		CN	5,286,985	02/15/94	Taddiken			
		co	5,310,707	05/10/94	Oishi et al.			
		СР	5,326,721	07/05/94	Summerfelt			
		ca	5,404,581	04/04/95	Honjo			
	1	CR	5,418,389	05/23/95	Watanabe			
	1	cs	5,436,759	07/25/95	Dijaii et al.			
	1	СТ	5,576,879	11/19/96	Nashimoto			
	1	CU	5,606,184	02/25/97	Abrokwah, et al.			
		CV	5,640,267	06/17/97	May et al.			
		cw	5,674,366	10/07/97	Hayashi et al.			
	1	сх	5,729,641	03/17/98	Chandonnet et al.	1		
	1	CY	5,790,583	08/04/98	Но			•
	\dagger	cz	5,825,799	10/20/98	Ho et al.			
	+	DA	5,857,049	01/05/99	Beranek et al.			
	+-	DB	5,874,860	02/23/99	Brunel et al.			
-	1	DC	5,926,496	07/20/99	Ho et al.		-	
	1	DD	5,937,285	08/10/99	Abrokwah, et al.			
		DE	5,981,400	11/09/99	Lo			
	+-	DF	5,990,495	11/23/99	Ohba	-		
	+-	DG	6,002,375	12/14/99	Corman et al.	+		
		DH	6,008,762	12/28/99	Nghiem	+		· · · · · · · · · · · · · · · · · · ·
		DI	6,055,179	04/25/00	Koganei et al.	- 		
	+-	DJ DJ	6,107,653	08/22/00	Fitzgerald	+		
		DK	6,113,690	09/05/00	Yu et al.	 		-
		DL	6,114,996	09/05/00	Nghiem			
		DM	6,121,642	09/19/00	Newns			
		DN	6,128,178	10/03/00	Newns			
_		DO	6,143,072	11/07/00	McKee et al.			
		DP	6,184,144	02/06/01	Lo			
		DQ	6,222,654	04/24/01	Frigo	-		

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	MB	5,528,057	06/18/96	Yanagase et al.			
	мс	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			
	мн	5,073,981	12/17/91	Giles et al.			
	МІ	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	Ho et al.			
	мк	6,362,017	03/26/02	Manabe et al.			
	ML	6,242,686	06/05/01	Kishimoto et al.			
	ММ	5,689,123	11/18/97	Major et al.			
	MN	5,670,800	09/23/97	Nakao et al.			
	мо	5,067,809	11/26/91	Tsubota ′			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			
	МТ	6,093,302	07/25/00	Montgomery			
	MU	6,372,813	04/16/02	Johnson et al.			
	MV	5,608,046	03/04/97	Cook et al.			
	MW	5,955,591	09/21/99	Imbach et al.			
	МХ	6,022,963	02/08/00	McGall et al.			
	MY	6,083,697	07/04/00	Beecher et al.			
	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert			*
	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			
	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina			
	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.			
	NJ	5,280,013	01/18/94	Newman et al.			
	NK	6,348,373 B1	02/19/02	Ma et al.			
	NL	6,339,664 B1	01/15/02	Farjady et al.			
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.			
	NP	6,011,641	01/04/00	Shìn et al.			
	NQ	6,340,788 B1	01/22/02	King et al.			
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	SB	5,395,663	03/07/95	Tabata et al.			
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	SD	5,452,118	09/19/95	Maruska			-
	SE	5,889,296	03/30/99	Imamura et al.			
	SF	6,300,615 B1	10/09/01	Shinohara et al.			
	SG	6,232,910 B1	05/15/01	Bell et al.		İ	
	SH	5,686,741	11/11/97	Ohori et al.			
	SI	4,959,702	09/25/90	Moyer et al			
	SJ	6,100,578	08/08/00	Suzuki			
	SK	6,410,947 B1	06/25/02	Wada			
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	SM	6,461,927 B1	10/08/02	Mochizuki et al.	1		
	SN	6,462,360 B1	10/08/02	Higgins, Jr. et al.	<u> </u>		
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	SP	5,981,980	11/09/99	Miyajima et al.	-		
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 	SU	6,319,730 B1	11/20/01	Ramdani et al.	1		
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 	sw	6,312,819 B1	11/06/01	Jia et al.			
	SX	5,119,448	06/02/92	Schaefer et al.	 		
	SY	4,120,588	10/17/78	Chaum		-	
	SZ	5,194,917	03/16/93	Regener		-	1-0
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 	ТВ	5,953,468	09/14/99	Finnila et al.			
	TC	5,561,305	10/01/96	Smith	 		
	TD	5,896,476	04/20/99	Wisseman et al.		-	-
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	TF	6,320,238 B1	11/20/01	Kizilyalli et al.		 	
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 	TH	5,760,427	06/02/98	Onda	-	-	
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 	TJ	5,668,048	09/16/97	Kondo et al.			
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	TQ	6,103,403	08/15/00	Grigorian et al.	<u> </u>		

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	UP	5,623,439	04/22/97	Gotoh et al.			
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ATA!	LIST OF REFERENCES CITED BY APPLICANT			Jamal Ramdani					
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	*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through ditation if not in conformance and not considered. Include copy of this form with next communication to applicant.								